

**IN THE UNITED STATES PATENT AND TRADEMARK OFFICE**

Application No.: 10/553,573  
Applicants: Christian DUSSARRAT et al.  
Filed Internationally: April 8, 2004  
US National: October 17, 2005  
Title: METHODS FOR PRODUCING SILICON NITRIDE FILMS  
BY VAPOR-PHASE GROWTH  
TC/A.U.: 1715  
Examiner: Elizabeth A. Burkhart  
Docket No.: Serie 6070  
Customer No.: 40582

**AMENDMENT**

Commissioner for Patents  
P.O. Box 1450  
Alexandria, VA 22313-1450

In response to the Office Action mailed September 28, 2010, having a shortened statutory period for response set to expire on December 28, 2010 and an extended time for response set to expire on January 28, 2011 in view of a 1-month extension of time, Applicants respectfully request reconsideration of the present application in view of the following amendments and/or remarks:

**Amendments to the Claims** begin on page 2 of this paper.

**Remarks** begin on page 5 of this paper.